1 of 1 **Application Number** Substitute for FORM PTO-1449 10/083,809 U.S. Department of Commerce Patent and Trademark Office Filing Date INFORMATION DISCLOSURE STATEMENT 2/26/2002 BY APPLICANT (Use several sheets if necessary) First Named Inventor Sergey Lopatin Attorney Docket No. P1409 Sheet 1 of 1 U.S. PATENT DOCUMENTS Examiner CitcNo. U.S. Patent Name of Patentee or Applicant Date of Publication of Pages, Columns, Lines, Document of Cited Documents Cited Document MM-DD-YYYY Where Relevant Passages or Initial Number Relevant Figures Appear 3/6/2001 1 6,197,181 B1 Chen, Lin Lin 2/8/2000 6,022,808 Nogami, et al. FOREIGN PATENT DOCUMENTS Cite Date of Publication Examiner Name of Patentee or Pages, Columns, Lines, Foreign Patent Applicant of Cited of Cited Document Where Relevant Initials' No. Document MM-DD-YYYY Office Number document Passages or Relevant Code Figures Appears OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS Examiner Cite Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title Initials' of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-No. issue number(s), publisher, city and/or country where published. PETER VAN ZANT, "Microchip Fabrication: A Practical Guide to Semiconductor Processing", 3rd Ed., p. 392 and 397 (1997) A. Krishnamoorthy, D. Duquette and S. Murarka, "Electrochemical Codeposition and 2 Electrical Characterization of a Copper-Zinc Alloy Metallization", in edited by Adricacos, et al., Electrochem Society Symposium Proceedings, Vol. 99-9, May 3-6, Seattle, p. 212 J. Cunningham, "Using Electrochemistry to Improve Copper Interconnect", in 3 Semiconductor International, Spring 2000 (May) 4 L. Chen and T. Ritzdorf, "ECD Seed Layer for Inlaid Copper Metallization" in edited by Andricacos, et al., Electrochem Society Proceedings, Vol. 99-9, May 3-6, Seattle, p. 122 Date Considered: Examiner Signature: *EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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